University of California at Berkeley College of Engineering Dept. of Electrical Engineering and Computer Sciences

EE 105 Midterm I

Spring 2006

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Guidelines

- Closed book and notes.
- One-page information sheet allowed.
- There are some useful formulas in the end of the exam.
- The values of common parameters are listed at the beginning of next page.

Please use the following parameters for all problems unless specified otherwise:

 $\phi_{n+} = 550 \text{ mV}, \ \phi_{p+} = -550 \text{ mV}, \ V_{th} = 26 \text{ mV}$ $\varepsilon_{\text{Si}} = 11.7, \ \varepsilon_{\text{SiO2}} = 3.9, \ \varepsilon_0 = 8.854 \times 10^{-14} \text{ F/cm},$ $q = 1.6 \times 10^{-19} \text{ C}, \ n_i = 10^{10} \text{ cm}^{-3}.$

- (1) Consider a silicon PN junction diode with an N-doping concentration of 10^{16} cm⁻³ and a P-doping concentration of 10^{18} cm⁻³. Their cross-sectional area of the diode is 100 μ m². Assume the reverse saturation current of the diode is 10^{-14} Amp. The diode is forward biased at 0.7V.
 - a) [10 pt] Find the dynamic resistance at this bias.
 - b) [10 pt] Find the depletion capacitance at this bias.
- (2) Consider a MOS capacitor with a P+ polysilicon gate and an N-doped substrate with a doping concentration of 10^{16} cm⁻³. The thickness of the oxide is 20 nm.
 - a) [10 pt] Find the threshold voltage.
 - b) [10 pt] Which mode is the MOS capacitor in when its gate is biased at 1 V?
 - c) [10 pt] What is the maximum capacitance per unit area?
 - d) [10 pt] What is the minimum capacitance per unit area?
- (3) [10 pt] For the MOS capacitor in Problem (2), plot the charge density distribution as a function of position when the gate is biased at -2V. Please be as quantitative as possible. Show the positions of all charges, and show the magnitude and polarity of the charges.
- (4) [10 pt] If the P+ gate of the MOS capacitor in Problem (2) is replaced by a metal whose electrostatic potential is 0V. What is the threshold voltage of the new MOS capacitor?
- (5) Consider an N-MOSFET with an N+ polysilicon gate on P-type substrate ($N_a = 10^{17}$ cm⁻³). The source is grounded, and the drain is biased at 5V. The transistor has a gate length of 1 µm, and a width of 10 µm. The thickness of gate oxide is 10 nm. For simplicity, assume the channel-length modulation parameter $\lambda = 0$.



- a) [10 pt] At what gate voltage does the transistor turn on, i.e., start to have significant current flowing between source and drain?
- b) [10 pt] Find the drain current when the gate is biased at 2V.

Some equations

Mass-action law $n \times p = n_i^2(T)$



Diffusion capacitance: $C_d = \frac{1}{2} \frac{q l_D}{kT} \tau$

Threshold voltage (NMOS)

NMOS equations:

$$\begin{split} &I_{D} = 0, \quad V_{GS} < V_{Tn} \\ &i_{D} = \frac{W}{L} \mu C_{ox} \bigg(v_{GS} - V_{Tn} - \frac{V_{DS}}{2} \bigg) v_{DS} (1 + \lambda V_{DS}), \quad V_{GS} > V_{Tn}, V_{DS} < V_{GS} - V_{Tn} \\ &i_{D} = \frac{W}{L} \frac{\mu C_{ox}}{2} (v_{GS} - V_{Tn})^{2} (1 + \lambda V_{DS}), \quad V_{GS} > V_{Tn'}, V_{DS} > V_{GS} - V_{Tn} \end{split}$$

MOS capacitances in saturation $C_{gs} = (2/3)WLC_{ox} + C_{ov}$ $C_{ov} = L_DWC_{ox}$

MOS signal parameters:

$$g_m = \frac{\partial i_D}{\partial v_{GS}}\Big|_{V_{GS}, V_{DS}} = \mu C_{ox} \frac{W}{L} (V_{GS} - V_{Tn}) (1 + \lambda V_{DS}) \approx \mu C_{ox} \frac{W}{L} (V_{GS} - V_{Tn})$$

$$r_{o} = \left(\frac{\partial i_{D}}{\partial v_{DS}}\Big|_{V_{GS}, V_{DS}}\right)^{-1} \approx \frac{1}{\lambda I_{DS}}$$

$$g_{mb} = \frac{\partial i_D}{\partial v_{BS}} \bigg|_Q = \frac{\gamma g_m}{2\sqrt{-V_{BS} - 2\phi_p}}$$

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$$q := 1.6 \cdot 10^{-19} \quad ni := 10^{10} \quad Vth := 0.026$$

$$\epsilon 0 := 8.854 \cdot 10^{-14} \quad \epsilon s := 11.7 \cdot \epsilon 0 \quad \epsilon ox := 3.9 \cdot \epsilon 0$$

$$\mu m := 10^{-4} \quad nm := 10^{-7} \quad mV := 10^{-3}$$

$$\mu_{\perp} n := 1450 \text{ cm}^2/\text{V-sec}$$
(1) (a) Is := 10⁻¹⁴

$$Id(Vd) := Is \left(\exp\left(\frac{Vd}{Vth}\right) - 1 \right)$$

$$Id(0.7) = 4.927 \times 10^{-3}$$

$$r_{-}d := \frac{Vth}{Id(0.7)} \quad r_{-}d = 5.278 \quad \Omega$$
(b) Nd := 10¹⁶ Na := 10¹⁸ Area := 100 \cdot \mu m^2
$$\phi n := 60 \cdot mV \cdot log\left(\frac{Nd}{ni}\right) \qquad \phi n = 0.36$$

$$\phi p := -60 \cdot mV \cdot log\left(\frac{Na}{ni}\right) \qquad \phi p = -0.48$$

$$\phi b := \phi n - \phi p \qquad \phi b = 0.84$$

$$xd(Vd) := \sqrt{\frac{2 \cdot \epsilon s \cdot (\phi b - Vd)}{q} \cdot \left(\frac{1}{Na} + \frac{1}{Nd}\right)} \qquad xd(0.7) = 1.353 \times 10^{-5}$$
(2) Nd := 10¹⁶ tox := 20 \cdot nm
$$\phi n := 60 \cdot mV \cdot log\left(\frac{Nd}{ni}\right) \qquad \phi n = 0.36$$

$$\phi p := -550 \cdot mV$$

V_FB :=
$$\phi n - \phi pp$$

(a) Xd max := $\sqrt{\frac{2 \cdot \epsilon s \cdot (2 \cdot \phi n)}{2 \cdot \epsilon s \cdot (2 \cdot \phi n)}}$ Xd max = 3.053×10^{-5}

$$Xd_max := \sqrt{\frac{1}{q \cdot Nd}} \qquad Xd_max = 3.053 \times 10^{-10}$$

$$Qb_max := q \cdot Nd \cdot Xd_max$$

$$Cox := \frac{\varepsilon ox}{tox}$$

$$V_Tp := V_FB - 2 \cdot \phi n - \frac{Qb_max}{Cox} \qquad V_Tp = -0.093$$

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(b) 1V is greater than flatband voltage --> the MOS is in accumulation mode

(c) Maximum capacitance is simply Cox:

Cmax := Cox (d) Cb_min := $\frac{\epsilon s}{Xd_max}$ Cmin := $\frac{Cox \cdot Cb_min}{Cox + Cb_min}$ Cmin = 2.835 × 10⁻⁸ F/cm²

(3) -2V is more negative than threshold (-0.093V), so it is in inversion. The charge on the semiconductor side include a fixed donor charges from the semiconductor-oxide interface to the maximum depletion width, Xd_max and the inversion hole charges at the interface, Qp. The gate charge is equal to the total charge with opposite sign.

$$V_{GB} := -2$$

$$Qp := -Cox \cdot (V_{GB} - V_{Tp})$$

$$Qp = 3.293 \times 10^{-7}$$

$$C/cm^{2}$$

$$\rho_{b} := q \cdot Nd$$

$$\rho_{b} = 1.6 \times 10^{-3}$$

$$C/cm^{3}$$

$$Qg := -Qp - \rho_{b} \cdot Xd_{max}$$

$$Qg = -3.781 \times 10^{-7}$$

$$C/cm^{2}$$

 $Xd_max = 3.053 \times 10^{-5}$



(4) Flatband voltage and threshold voltage is shifted by the same amount:

 $\phi m := 0$

$V_FB_m := \phi n - \phi m$	$V_FB_m = 0.36$	
$\Delta V_FB := V_FB_m - V_FB$	$\Delta V_FB = -0.55$	
$V_Tp_m := V_Tp + \Delta V_FB$	$V_Tp_m = -0.643$	V

(5) Na :=
$$10^{17}$$
 tox := $10 \cdot \text{nm}$ W := $10 \cdot \mu\text{m}$ L := $1 \cdot \mu\text{m}$
 $\phi p := -60 \cdot \text{mV} \cdot \log\left(\frac{\text{Na}}{\text{ni}}\right)$ $\phi p = -0.42$
 $\phi \text{nn} := 550 \cdot \text{mV}$
 $V_FB := \phi p - \phi \text{nn}$ $V_FB = -0.97$
 $Xd_max := \sqrt{\frac{2 \cdot \epsilon s \cdot (-2 \cdot \phi p)}{q \cdot \text{Na}}}$ $Xd_max = 1.043 \times 10^{-5}$
 $Qb_max := -q \cdot \text{Na} \cdot Xd_max$
 $Cox := \frac{\epsilon O x}{to x}$
 $V_Tn := V_FB - 2 \cdot \phi p - \frac{Qb_max}{Cox}$ $V_Tn = 0.353$

(a) The NMOS FET is turned on when the gate voltage is equal to the thresold voltage

 $V_Tn = 0.353$

(b) V_GS := 2

 $V_DS := 5$

 $V_DS_sat := V_GS - V_Tn$ $V_DS_sat = 1.647$

Since V_DS is greater than V_DS_sat, the FET is in saturation

$$I_DS(V) := \frac{W}{L} \cdot \frac{\mu_n \cdot Cox}{2} \cdot (V_GS - V_Tn)^2 \qquad I_DS(5) = 6.789 \times 10^{-3} \text{ Amp}$$